

ULVAC

Unlocking New Possibilities —
The Future of Innovation Driven by Vacuum

ULVAC



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새로운 가치창조를 통해 한국사회에 공헌하는 기업
한국알박(주)입니다.



한국알박(주) 대표이사 사장

최승수

한국알박은 세계 최고 수준의 진공 기술력을 기반으로 반도체, 디스플레이, 2차전지 등 첨단 산업의 발전에 기여해 왔으며, 축적된 기술과 경험을 토대로 최상의 제품과 기술 지원을 제공해왔습니다.

30년의 성과를 넘어 새로운 30년을 준비하기 위해 한국알박은 'Vision 2032 가능성의 장'을 중심으로 디지털 전환, 지속가능 경영, 글로벌 확장, 사람 중심의 경영이라는 네 가지 전략을 실행해 나가고 있습니다. 제조혁신과 기술 고도화를 통해 글로벌 경쟁력을 한층 강화하고, 자율과 책임이 조화를 이루는 조직 문화를 구축해 나가겠습니다.

앞으로도 고객의 목소리에 귀 기울이며, 신뢰와 사람, 열정을 바탕으로 지속 가능한 성장과 국가 경쟁력 향상에 기여하는 기업으로 나아가겠습니다.

한국알박과 함께 만들어갈 미래에 변함없는 관심과 성원을 부탁드립니다.

Unlocking New Possibilities — The Future of Innovation Driven by Vacuum



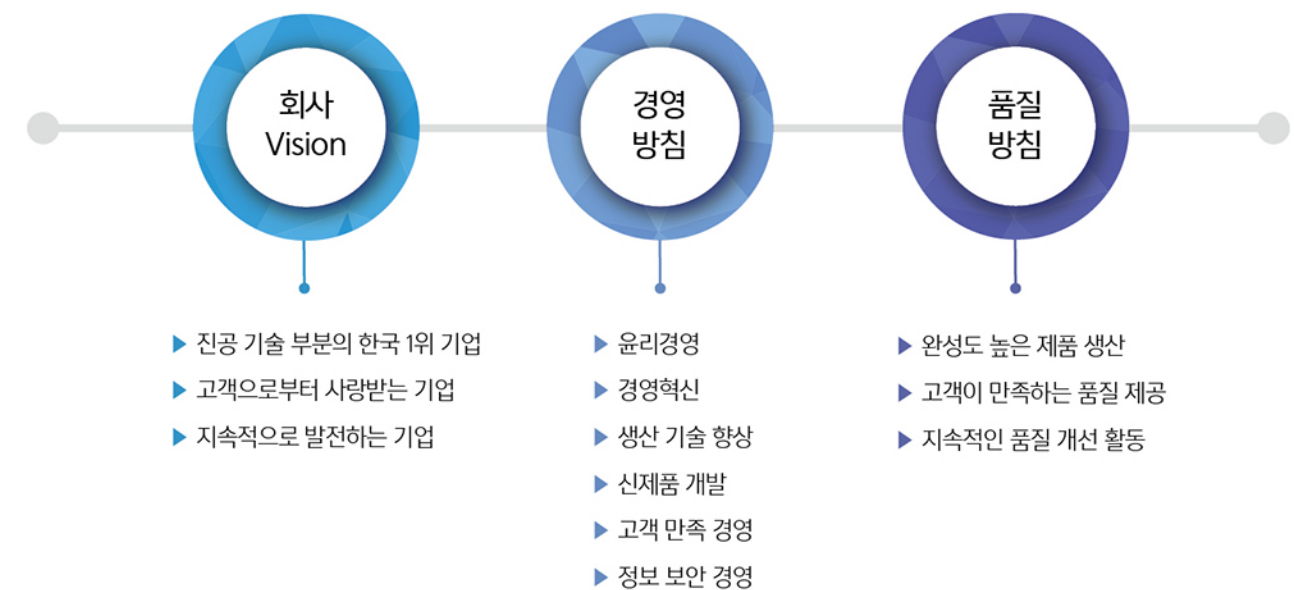
Our missions are Technology Development,
Customer's satisfaction & Future creating



ULVAC

풍요로운 미래, 가치있는 기술 _ 한국알박

세계진공기술 1위기업을 지향하는 한국알박은
최고의 첨단기술력과 노하우를 바탕으로
세계 최강의 기술이될 수 있도록
최선의 지원을 펼치고 있습니다.
성공신화를 창조하는 기업파트너 한국알박과
미래를 함께하십시오.



Company History

R&D, Manufacturing in Korea



한국알박은 1995년 7월 설립 이래 진공전문 Maker로서 다양한 산업분야에 헌신하고 있습니다. 현재 본사는 경기도 평택시 청북면 어연한산 지방산업단지 내 위치하고 있으며 5천 평 부지에 반도체, 전자기기 장비 위주의 제조설비와 크린룸을 보유하고 있습니다.

그리고 현곡산업단지 내 1만여 평 규모의 부지에 8세대 이상의 Sputter 장치를 제조할 수 있는 제조설비 및 크린룸을 보유하고 있습니다. 그 외 분당, 부산에 영업소를 두고 있으며, 구미, 화성, 탕정, 파주에 고객지원센터를 설립하여 고객과 가까운 곳에서 신속한 서비스가 가능하도록 고객중심의 전국네트워크 망을 구축하고 있습니다. 뿐만 아니라 ISO9001, ISO14001, ISO 27001, ISO 45001의 인증취득과 2005년 외국인 투자유치 유공자 대통령 표창, 2010년 대·중소기업 동반성장 국무총리 표창, 경실련 주관의 바른 외국기업상 최우수상, 2015년 1억불 수출의 탑 수상을 통해 대내외적으로 경제, 사회적 성과를 인정받고 있습니다.

History

- | | |
|--|---|
| 1995. 07 / 한국알박(주) 설립 (ULVAC KOREA, LTD.) | 2006. 10 / 탕정사무소 설립 |
| 08 / 서울고객지원 Center설립 [SEOUL CSC] | 11 / 현곡 제5공장 준공 |
| 1997. 06 / 구미 고객지원 Center 설립 [구미 CSC] | 2007. 05 / 화성 고객지원 Center 설립 (화성CSC) |
| 07 / 한국알박(주) 츠나시마 카츠오(綱島勝男) 사장 취임 | 2008. 07 / 자회사 [한국알박머터리얼즈(주)] 설립 |
| 2000. 08 / 평택 제1공장 준공 (서울 CSC → 평택공장 이전) | 2011. 07 / 한국소재연구소 설립 |
| 09 / 한국알박(주) 백충렬(白忠烈) 대표이사 사장 취임 | 2012. 07 / 대전영업소 설립 (광주 → 대전영업소 이전) |
| 2001. 04 / 평택 제2공장 준공 | 2016. 05 / 한국알박(주) 백충렬(白忠烈) 회장 취임 |
| 2003. 11 / 평택 제3공장 준공 | / 한국알박(주) 후지야마 준키(藤山潤樹) 대표이사 사장 취임 |
| 2004. 07 / 자회사 [한국알박정밀(주), PS Tech.(주)] 설립 | 2018. 07 / 한국알박(주) 김선길(金善吉) 대표이사 사장 취임 |
| / 광주영업소, 부산영업소 설립 | 2021. 09 / 분당기술개발센터 설립 (서울 → 분당 이전) |
| 08 / 이전 고객지원 Center 설립 (이전CSC) | 2022. 11 / 평택 고객 고객지원 Center 설립 (고객CSC) |
| 2005. 04 / 현곡 제4공장 준공 (현곡지방산업단지) | 2024. 05 / Technology Center 평택 준공 |
| 08 / 파주 고객지원 Center 설립 (파주CSC) | 2025. 07 / 한국알박(주) 최승수(崔承洙) 대표이사 사장 취임 |
| 12 / UF TECH(주) 인수 | / 한국알박(주) 김선길(金善吉) 대표이사 회장 취임 |

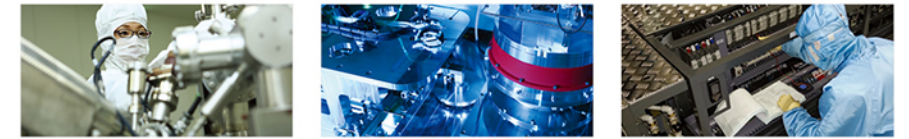
인증 및 수상

- | | |
|--------------------------------------|---|
| 2001 / ISO9001 인증 취득 | |
| / 모범 납세자 경제부총리 표창 수상 | |
| 2003 / IT 우수기업 중소기업청 표창 수상 | |
| 2005 / 백충렬 대표이사 모범기업인 표창 수상 | |
| / ISO 14001인증 취득 | |
| / 무역의 날 천만불 수출의 탑 수상 | |
| / 백충렬 대표이사 투자유치유공자 대통령 표창 수상 | 2017 / LG Display 주관 동반성장 Award 수상 |
| 2006 / 대통령 직속 중소기업 특별위원회 감사패 | 2018 / LG Display 주관 Best Partner Award |
| 2007 / 경실련 바른외국기업상 우수상 수상 | 2019 / 평택시 주관 사회복지향상 표창 수상 |
| 2008 / 경기도 투자유치 우수기업인상 수상 | 2020 / LG Display Best Partner Award 수상 |
| 2009 / 대일수출 유망기업 선정 | / 통계청 주관 통계유공자 경인정장 표창 수상 |
| 2010 / 경기도 성실납세법인 인증서 수상 | 2021 / ISO 45001 인증 |
| / 백충렬 대표이사 대·중소기업 협력대상 국무총리 표창 수상 | / 제55회 납세자의 날 정부 포상 전수식 |
| / 경실련 바른외국기업상 최우수상 수상 | / 대통령 산업포장 수상 |
| / 우수봉사기업 평택시장 표창 수상 | / 2021 한국 디스플레이 산업협회 공로상 수상 |
| 2011 / ISO 27001 인증 취득 | 2022 / LG Display 주관 안전관리부문 최우수협력사 수상 |
| / 지식경제부 일하기 좋은 기업 선정 | 2023 / 대한민국 일자리 으뜸기업 대통령 인증패 및 |
| / 국회국방위원장 주관 봉사상 표창 | 노동부장관 인증서 수상 |
| 2012 / KOSHA/OHSMS 안전보건경영 인증 취득 | / 한국가치경영대상 산업통상자원부 장관상 수상 |
| / 지식경제부 자율준수 무역거래자 지정 | / 평택시 주관 지역사회 나눔문화 표창장 수여 |
| / 한국산업안전보건공단 주관 2012년도 안전보건활동 장려상 수상 | 2024 / 평택시 주관 우수납세자 수상 |
| / 한국무역협회 7000만불 수출의 탑 수상 | / 대한민국 일자리 으뜸기업 대통령 인증패 및 |
| 2014 / 산업통상자원부 주관 자율준수 무역 거래자 지정 | 노동부장관 인증서 수상 |
| / 혁신 우수협력사 수상 | / 경기도 주관 투자유치와 지역경제 발전공로 표창장 수여 |
| 2015 / 무역의 날 1억불 수출의 탑 수상 | 2025 / 경기도 주관 유공납세자 수상 |
| 2016 / 삼성전자 16년도 상생협력DAY 혁신우수협력사 수상 | / SK Hynix 주관 우수협력사 수상 |
| / 한국디스플레이협회장상 수상 | / 삼성전자 주관 공로상 수상 |
| | / SAMSUNG OUTSTANDING COLLABORATION AWARD |



Touch the Future with Dream Technology

Building a flourishing future by creating innovative solutions to deliver industrial and scientific advancement



Semiconductor Production Equipment

Aims to expand its semiconductor equipment market share by leveraging advanced miniaturization, deposition, and non-volatile memory technologies to support next-generation devices in a smart society.

Electronic Device Production Equipment

Seeks to expand its electronic device equipment business by advancing compact packaging and vacuum technologies that support IoT, AI, EV, and next-generation devices such as non-volatile memory, 3D-ICs, sensors, and opto-telecom components.

Industrial Vacuum Equipment

Leverages decades of vacuum technology expertise to provide thermal vacuum solutions that support high-value manufacturing across diverse industries such as automotive, pharmaceuticals, food, and materials processing. ULVAC provides thermal vacuum solutions for high-value manufacturing across diverse industries.

VMS Production Equipment

Delivers advanced manufacturing solutions by applying its vacuum technologies to develop deposition equipment that supports EV batteries and displays, contributing to lighter, safer, and more resource-efficient products.

Vacuum Components

Strengthens its global business by leveraging comprehensive vacuum technology and a broad lineup of components, from pumps and measurement systems to power supplies and valves, supporting diverse industrial applications worldwide.

Semiconductor Production Equipment

Cutting-edge Products to Meet State-of-the-art Processing Requirements

Model : ENTRON-EX W300

Multi-chamber Sputtering Systems

Features

- ENTRON-EX W300 is the newest line-up developed based on existing. ENTRON-EX W300 in order to achieve high productivity.
- Line up with detailed model (TiN, CuRk) respond to various material.
- Up to 8 process chambers (PVD, ALD, CVD, etc.) and 2 chambers (Degas, cool).
- Mechanical throughput is 100wph or more using by ULVAC original new transfer robot.
- ENTRON-EX W300 S-type (Single core type) is suitable for mini-fab concept and ENTRON-EX W300 T-type (Tandem type) is good for mass production, they are flexible for customers' needs.
- ED-PMS system which monitor and administrate machine condition, and MESEC-BIT, which is no contact film thickness measurement tools.

Applications

- Advanced Semiconductor manufacturing equipment.



Model : RISE-300

Batch System to Remove Native Oxide

Features

- Damage-free (remote plasma and low-temperature process).
- High throughput and low CoO.
- Processing in batches of fifty wafers.
- Superior uniformity of etching (5% or less per batch).
- Easy maintenance.
- Small foot print compare to cluster type equipment.
- 50% lower self-aligned contact resistance compared to current wet process.
- The smallest foot print.

Applications

- Pre-cleaning for self-aligned contact (SAC) formation.
- Pre-cleaning for capacitor formation.
- Pre-cleaning for epitaxial growth.



Industrial Vacuum Equipment

Wide Range of Product Applications Made Possible by ULVAC Technologies

Model : DFB Freeze Drying/Vacuum Drying System

Features

- Touch-panel operation, operation display, warning display, maintenance display.
- Shelf temperatures can be controlled by programs.
- Completely automatic operation.
- Electronic expansion valve is provided standard.
- Stable vacuum control from primary to secondary drying.
- Standard lineup includes models supporting O/SIP.

Applications

- Freeze-drying processes for pharmaceutical products.



Model : COMBAT Compact Batch Type Furnace System

Features

- Maximum temperature 1300°C, Operation temperature 400 to 1250°C.
- Temperature uniformity is within ±5°C at 1000°C.
- Ultimate vacuum Not more than 3×10^{-3} Pa.
- Working vacuum High vacuum mode 10-2 Pa, Carrier gas mode 20 ~ 100Pa.
- Keeping the heating chamber in vacuum for high quality and repeatability of products.
- Carrier gas system is implemented to minimize metal evaporation.
- The heating chamber is kept in vacuum to prevent from oxidizing so that lifetime for internal parts of the heating chamber can be longer.
- Ultimate vacuum : Not more than 3×10^{-3} Pa.
- Working vacuum : High vacuum mode 10-2 Pa, Carrier gas mode 20 ~ 100Pa.

Applications

- Quenching, Tempering : various machine parts, parts for air plane.
- Brazing : Heat exchanger, machine parts, parts for air plane, vacuum interception.



Model : FSC Vacuum Sintering Furnace

Features

- Inline system configuration enables high-quality product manufacture.
- Inline system configuration increases productivity.
- Highly reliable system with extensive sales records.

Applications

- Computer drive system motors.
- Mobile phone capacitors.
- Edge chips for cutting tools.
- Precision parts (automotive, camera, sewing machine parts)



Model : H Diffusion Furnace

Features

- Can choose up to four different processes.
- Five zones heater control for highly uniform soaking.
- Easy loading with boat elevator and soft-lander unit.
- Space saving design.
- Original control system dedicates easy and reliable operation.

Applications

- Pyrogenic wet oxide, wet oxide, dry oxide, Phosphorus and Boron doping with POCl_3 or BBr_3 , and anneal.



Electronic Device Production Equipment

Sputtering, Plasma CVD and High Vacuum Evaporation Systems Make Up the Main Product Line

Model : ei

Batch-type High Vacuum Evaporation System

Features

- Supports various evaporation sources(i.e.EB, RH, EB+RH etc.).
- Substrate holders complying with each process(i.e.lift-off, planetary, satellite etc.).
- Supports various substrates; substrates size from Ø2in to 12in, rectangular substrates, Si, Compounds, glass and ceramics.
- Improved Lift-off function and increased number of loadable substrates(EVD-600LP).

Applications

- Compound-related devices of Power devices.
- LED, LD and high speed devices.
- Various R&D and Other general electronic devices.



Model : NE

Load Lock Type Dry Etcher System

Features

- Higher Through-put (by 140% than conventional systems).
- ICP with magnetic field high density plasma source which has over 600 delivery record in compound semiconductor market is equipped.
- Proprietary Star electrode*2 which has self-cleaning function for deposited material from RF window is equipped.
- High maintenance capability, stability, reliability are achieved through re-deposition preventative designing.
- Dry etching technology availability for various process application. (GaN, Sapphire, Metal, ITO, SiC, AlN, ZnO, 4 elements compound semiconductor materials, etc.).
- Various Option availability.



Model : NA

Luminous NA Series

Features

- High does ion implant stripping process and polymer removal process of 10E16 or higher level that are necessary for critical process for next generation wafers can be implemented free of damages.
- Chamber construction is arranged most suitably for an F-based gas addition process, and particle-free treatment is possible. Therefore, it is suitable to construct an extremely wide range of processes from normal PR to high does ion implant stripping process, organic films (such as PI and DFR) peeling and oxidized film etching.
- A simple system construction is adopted, achieving "excellent maintainability and reliability" and "low cost" at the same time.
- Flexible system construction is possible (μ wave, RIE, and μ wave + RIE), allowing a wide range of transfer channel selection.
- Wafer size can be switched by simply changing the recipe setting, achieving very easy wafer size change.

Applications

- High does ion implant stripping process (10E16 or higher) and polymer removal in front end process.
- Wafer process that requires CF4 addition process (electronic parts and LEDs).
- Chip size package and bump process. ■ CCD color filter manufacturing process.



Model : ULDiS

Sputtering System for Optical Filters and Coating

Features

- Coating of the filters of good spectrum characteristics.
- Low processing temperature.
- Prevent arcing plasma by double cathodes ; AC sputtering.
- Precisely reproducible coating thickness.
- A wide variety of options including low-damage cathode.

Applications

- Mirror coating for DVD.
- Other optical filters including anti-reflection coatings.
- Mirror coating for DVD.
- Other optical filters including anti-reflection coatings.



SiC Power Device

Model : IH-860PSiC Ion Implanter

Features

- High Temperature ion implantation.
- Energy
 - 400Ke V (One valance ion)
 - 800Ke V (Two valance ion)
 - 1.2Me V (Three valance ion)
- Dual End Station.
- Chain Implantation by software.
- From R&D to mass production.



Model : Ailesic

SiC Extra High Temp Process Equipment Series

Features

- Dry/Net Oxidation (O₂, Pyrogenic).
- Oxynitriding/Post Oxidation Anneal (N₂O, NO).
- Max. Operational Temperature : 700-1350/1450/1650 degree C.
- Max. Heating/Cooling Rate : 20 degree C/min.
- Available Wafer Size : 4-6 Inch.
- Batch Size: 50/50/25 Wafers / Batch.
- Activation Anneal (N₂, Ar).
- Op Temp: 1200-1950 degree C.
- Max. Heating/Cooling Rate : 100 degree C/min.
- Available Wafer Size : 4-6 Inch.
- Batch Size: 25 Wafers / Batch.



Model : CS-200

Load lock type Sputtering System

Features

- Substrate transfer capability up to Ø300mm (Deposition performance up to Ø200mm).
- Automatic multi-layered deposition by recipe control.
- Capable of automatic substrate transfer by simply loading the substrate on to manipulator in the Load-lock chamber.
- Cassette chamber available five substrates stocker inside of load-lock chamber.
- Co-sputtering and Multi-layer deposition using multi cathodes.
- Bias-sputtering available with optional substrate Bias power supply.

Applications

- R&D.
- Small production purpose.



Model : uGmni

Combined deposition and etch modules' system of cluster type for advanced electronics

Features

- Multi types of sputter, etcher, asher & PE-CVD modules can be equipped.
- All types of above modules are made by ULVAC.
- Up to Ø300mm wafer is applicable.

Applications

(Examples follow)

- Power
- MEMS sensor
- Opt. device
- Packaging
- Communication
- Seed & metal layer sputtering
- PZT sputtering & etching
- VCSEL etching
- Descum ashing
- Insulated PE-CVD and etching



VMS Production Equipment

A Pioneer in Display Manufacturing Equipment with the Largest Share of Global Flat Panel Display Equipment Group

LCD & OLED Manufacturing Equipment / Roll coating system

Model : SMD

SMD series is a sputtering device for various membrane types such as metal, ITO, IGZO, etc.
We have delivered more than 1,000 units and are operating in various environments.
We can further improve reliability by reflecting the raw voices obtained from our rich performance in a timely manner.

Features

- Suggest the best platform for your application (Vertical/Cluster).
- Space-saving design.
- Easy to manage individual substrates such as film forming conditions.
- Cathode lineup corresponding to film-forming substances.
- Extensive membrane-forming processes supported by rich experience and data.

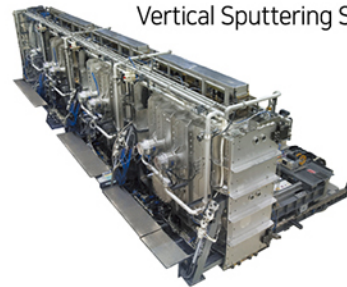
Applications

- Display (TFT, Smartphone, Thin TV (4K, 8K), OLED).

Sputtering Systems Single-substrate

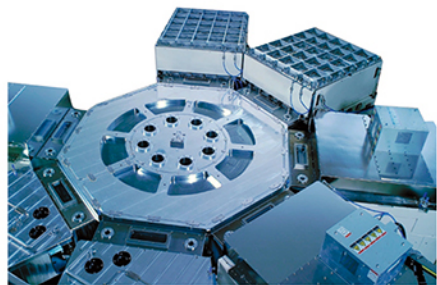


Vertical Sputtering Systems



Model : CMD

Single-substrate Plasma CVD Systems



CMD series are single-substrate CVD system for deposition of a-Si film, silicon oxide film and nitride film using SiH₄ or TEOS.

Features

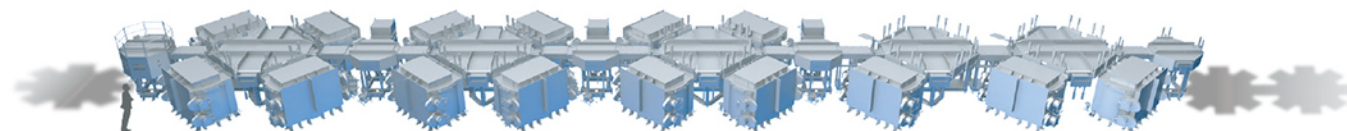
- Compared with the existing process temperature, the driving system of each unit and the development of vacuum transport robot have been developed to achieve stable transportation system.
- The long-term stable rate of TEOS(SiO₂) films can be obtained by improving the internal structure of the reaction chamber and the gas supply system.
- Due to the heating of the reaction gas path, the gas can be discharged to the excluded equipment, and the attachment of by-products to the piping can be suppressed without using the piping trap, thus reducing the maintenance time can be shortened.
- It is easy to manage individual substrates such as film forming conditions.

Applications

- Low temperature P-Si, a-Si TFT, Oxide TFT.

Model : ZELDA

Single-substrate Organic EL Manufacturing Systems



The ZELDA series introduces a series of cluster systems for mass production from experimental systems for organic EL materials development.

Applications

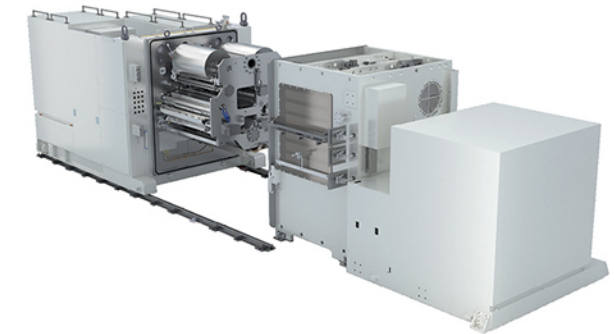
- Organic EL displays, organic EL lighting.

Model : EWE (for Film Capacitor)

RH Evaporation Roll Coater

Features

- Web Width : Up to 1050mm
- Evaporation Source : Resistance Heating type
- Thin web handling with high speed deposition : OPP 2.0μm - Depo speed 600m/min
- High speed patterning for self-security function : Pattern accuracy < 0.2±0.05mm : Depo speed 750m/min

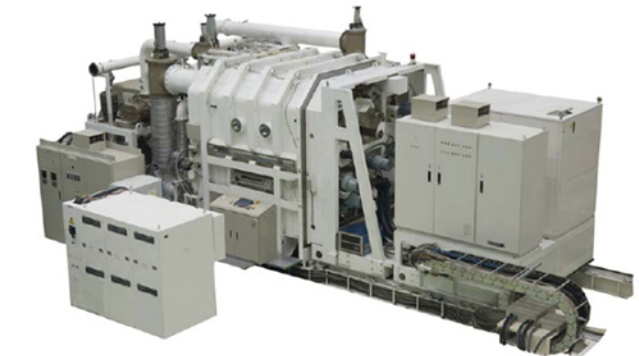


Model : EWA

IH Evaporation Roll Coater

Features

- Web Width : Up to 3300mm
- Evaporation Induction Heating Type
- Low pin-hole deposition with IH Heating
- Transparent barrier film (AlOx, SiOx) deposition



Model : EWK (for LiB/LiC)

RH Evaporation Roll Coater

Features

- Web Width : Up to 600mm
- Evaporation Source : Resistance Heating type
- High rate deposition : 20μm·m/min
- Li surface protection with passivation treatment



Vacuum Components

Cutting-edge Products to Meet State-of-the-art Processing Requirements

Leak Detector

Model I: HELIOT 901W1 / 901D2 / 904W2 / 904D3R / 904D4R

HELIOT 900 series is a leak detector which has high speed pumping capability and user-friendliness. Highest performance is committed in all kinds of leak tests.

Features

- High speed pumping capability 5L/sec helium in ULTRA flow mode.
- Tablet wireless remote control as standard.
- Simple and eye-friendly high-definition screen.
- Backing pump is selectable from oil rotary pump and dry scroll pump in different sizes.
- Mobile-friendly with maneuverable cart (904 series) and low height floor cart (901 series).
- Easy maintenance. Tool-free removal panel, easy access to each part and maintenance instruction movies installed.
- Aside from helium, hydrogen detection is possible in vacuum method.



Process gas monitor

Residual Gas Analyzer

Features

- **Model : Qulee CGM2-051/052/101/102**
For sputtering system for process control, quality control and yield ratio improvement.
- **Model : Qulee BGM2-101/102/201/202**
For various kind of evaporator and vacuum furnace for quality control and yield ratio improvement.
- **Model : Qulee HGM2-202/302**
For research & development equipment.
- **Model : Qulee RGM2-201F**
For etching and CVD system for process control, quality control, yield ratio improvement and end point monitoring.
- **Pumping System Qulee with YTP**
For wide range of usage from process control, residual gas analysis of various vacuum equipments to R&D.



Model : SH200 / ST200

Hot Cathode Gauge

New model of transducer type "G-RTAN Multi Ionization Gauge" that is capable of connection to different type sensor heads.

Features

- ULVAC own concept: Capable of connection of different measurement range sensor heads according to application.
- Compact: Significantly miniaturized compared to the previous model (56% reduction of controller volume). World's smallest class.
- High usability: Set point setting, condition check, etc. by connecting PC/Android.



Model : ELEC / COVOT-6-X5

Vacuum Transfer Robot

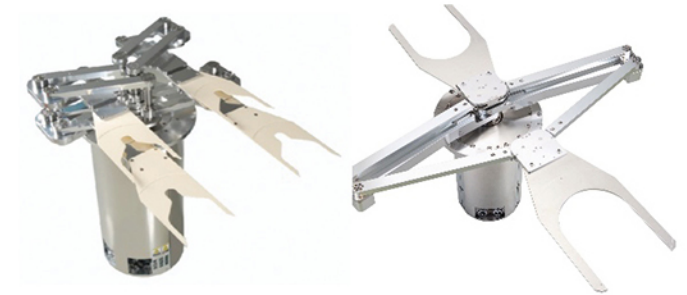
ULVAC's vacuum transfer robots, developed based on extensive expertise as a vacuum equipment manufacturer, offer clean and highly reliable performance in vacuum handling applications.

Features

- A wide range of arms are available to suit the stroke, turning radius, and number of boards to be transported.
- Enable to use in the high vacuum (10⁻⁶Pa~).

Applications

- Automatic wafer transfer for various semiconductor equipment.
- Wafer transfer for various vacuum.



Power Supply

Features

- High Power DC Power Supply Model : DC-10/20/30
- Low Power DC Power Supply Model : DC-2/4
- DC Pulse Power Supply Model : DPG-5/10
- RF Power Generator / Matching Box Model : RFS-1305N/1310N/1330N/1350N
- High Function EB Power Supply Model : HPS-510S/1000N



Dry Vacuum Pump

Model : LS120A / 300A / 600A / 1200A

Dry Pump which has both high pumping speed and low power consumption. Enable to select suitable pump from 4 different pumping speed model depending on the use condition.

Features

- **High pumping speed**
High pumping speed at near atmosphere pressure, and pumping down time can be drastically reduced.
- **Low power consumption**
ECO-SHOCK technology realizes low power consumption (C Type) at the ultimate pressure is the industry-leading 0.6kW or less (LS120A-C).
- **Low noise**
Built-in silencer achieves the noise level 61dB(A) or less.
- **Low running-cost**
No shaft sealing gas.



Vacuum Components

Cutting-edge Products to Meet State-of-the-art Processing Requirements

Oil Rotary Pump

Model : VS650B-A / 650B-W / 750B-A / 750B-W

Large size and low vibration (Single stage type)

Features

- Selectable from air and water cooled type. Oil cooler is used for oil temperature cooling for a air cooled model.
- Equipped with a cartridge-type oil mist filter inside the oil tank.
- Cleaning of the inside of the oil tank and replacement of the oil mist filter are easy.



Cryo Vacuum Pump

With proven reliability, excellent performance and quality, prompt and appropriate services, and many different models, our cryo pumps are ideal for production lines all over the world.

Features

- Ultra-clean vacuum
- High pumping speed
- Pumps all gases
- No liquid helium nitrogen
- Mounts in any orientation
- Compact design
- Quiet, easy, to operate
- Lower operating cost



Turbo Molecular Vacuum Pump

Controller integrated turbo molecular pump with magnetic bearings saves wiring work and installation space.

Features

- Controller integrated with the pump body
No wiring work between pump body and controller.
- Free mounting direction
Free mounting direction makes the system design flexible.
- 5 models from 1000L/s to 4000L/s class.
- Wide range and high flow for the light processes.
- Pump rotation variable from 25% to 100%
Enabling the pressure adjustment in a chamber.
- High durability and safety
Safety confirmation tests are passed, such as air rushing-in test and touch down test.



Small Vacuum Pumps

Features

- Diaphragm Type Vacuum Pump Model : DAP / DA / DAT / DAU / DTU
- Rocking Piston Type Dry Vacuum Pump Model : DOP
- Scroll Type Dry Vacuum Pump Model : DIS/DISL
- Multi-Stage Roots Type Vacuum Pump Model : RDA
- Oil-Sealed Rotary Vacuum Pump Model : GLD / GHD / GCD
- Mechanical Booster Pump Model : MBS



Charging System for Electric Vehicle

Cutting-edge products leading the market

Normal Charger

Model : UK-NC7W-TC/E



V1G, V2G Charger

Model : UK20GV-NC7W

- ▶ V1G : Unidirectional Smart Charging
- ▶ V2G : Vehicle-to-Grid



Fast Charger

Model: UK-QC50D-DC

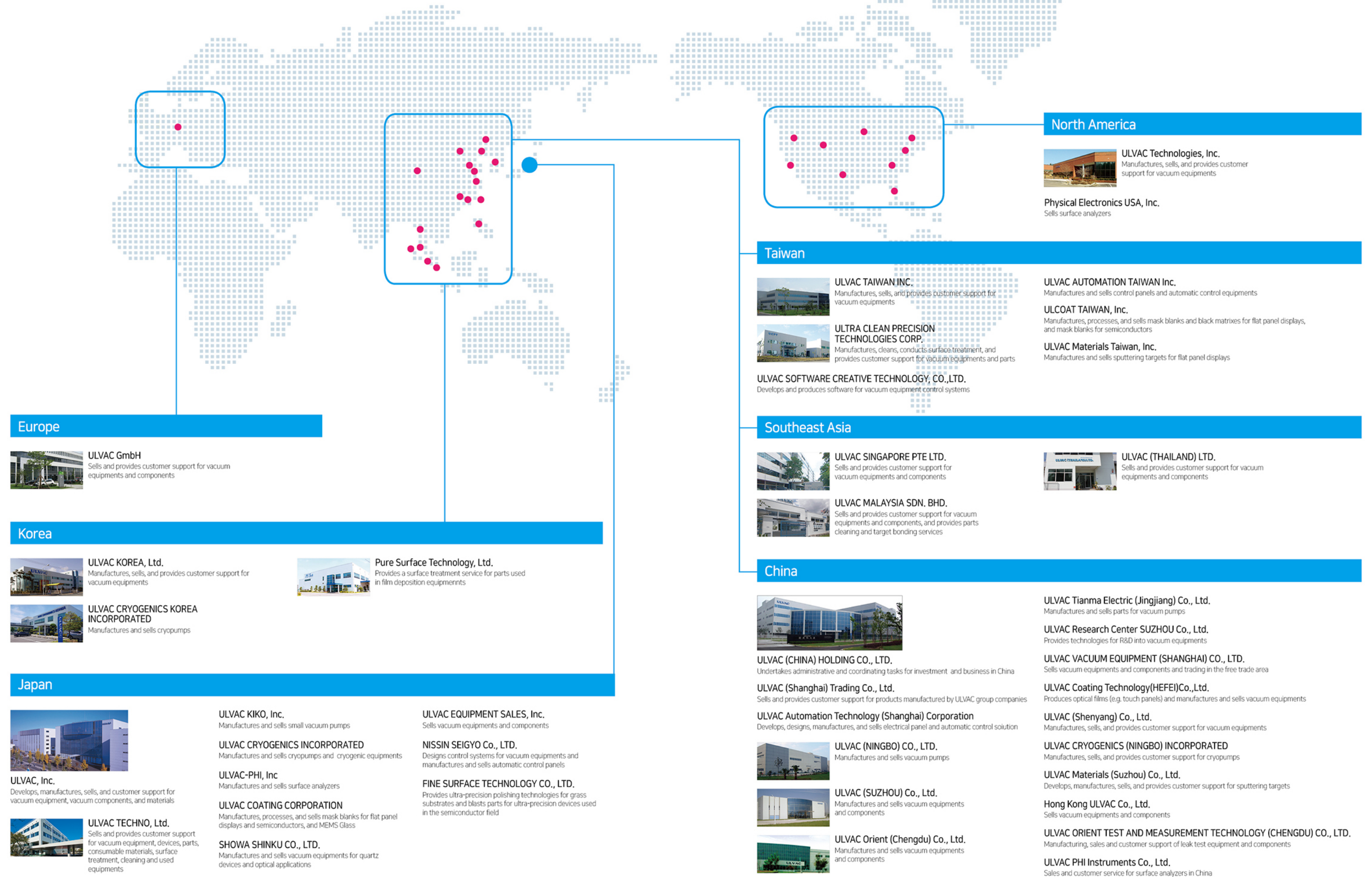


Quick Charger

Model: UK-QC100D-DC



ULVAC GROUP COMPANIES





ULVAC
ULVAC KOREA, Ltd.

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현곡공장 tel. 031_617_9500
17812 경기도 평택시 청북면 현곡산단로 123

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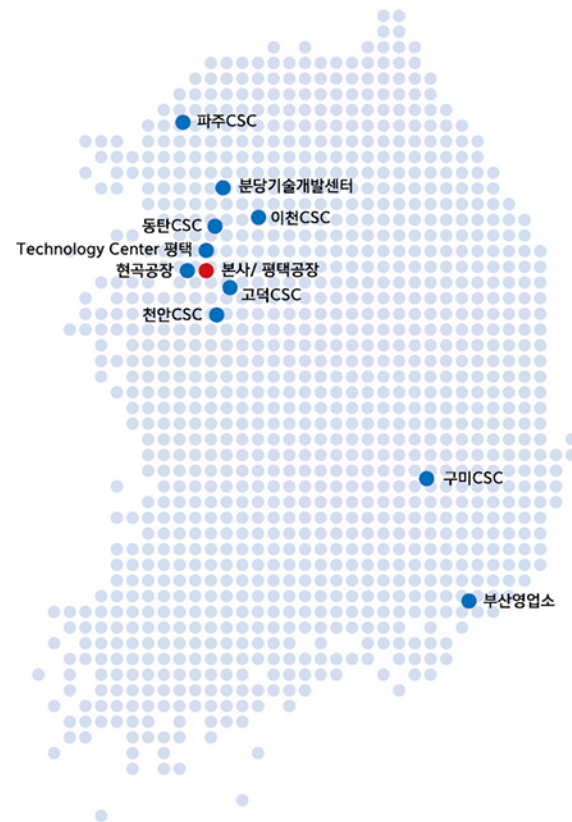
고덕CSC tel. 070_5148_7930
18014 경기도 평택시 고덕여업9길 42 센트리마 더퍼스트 1차 8층

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